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Docket No.: 060188-0751

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	:	Customer Number: 20277
Yoshiharu HIDAKA, et al.	:	Confirmation Number: 8259
Application No.: 10/754,518	:	Group Art Unit: 2814
Filed: January 12, 2004	:	Examiner: Thao X. Le

For: SEMICONDUCTOR SUBSTRATE, METHOD FOR FABRICATING THE SAME, AND
METHOD FOR FABRICATING SEMICONDUCTOR DEVICE

INFORMATION DISCLOSURE STATEMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed more than three months after the U.S. filing date AND after the mailing date of the first Office Action on the merits, but before the mailing date of a Final Rejection or Notice of Allowance.

CERTIFICATION PARAGRAPH

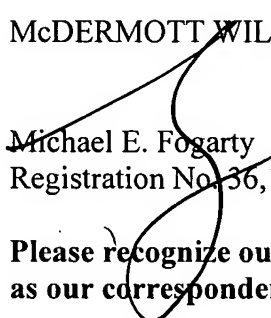
The undersigned certifies that each item of information contained in this Information Disclosure Statement was first cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this Information Disclosure Statement as described in 37 CFR 1.97(e)(1).

Each non-English language reference was cited in a corresponding foreign application search report and its relevance discussed therein. A copy of the foreign search report is attached for the Examiner's information.

Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

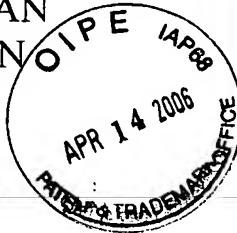
Respectfully submitted,

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 060188-0751		SERIAL NO. 10/754,518	
							
APPLICANT Yoshiharu HIDAKA, et al.							
FILING DATE January 12, 2004						GROUP 2814	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Document Number <small>Number-Kind Code² (if known)</small>	Publication Date <small>MM-DD-YYYY</small>	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
		US 5,185,965	02/16/1993	Ozaki			
		US 2001/0036738 A1	11/01/2001	Hatanaka et al			
		US 2002/0164934 A1	11/07/2002	Honda			
		US					
		US					
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		US					
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document <small>Country Codes - Number 4 - Kind Codes (if known)</small>	Publication Date <small>MM-DD-YYYY</small>	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation	
						Yes	No
		DE 43 31 727 A1	03/24/1994	DAITO SHOJI CO., LTD.; EMTEC CO.		GERMAN (w/ English Abstract)	
		JP 2000-082688	03/21/2000	MITSUBISHI MATERIALS SILICON CORP.		JAPAN (w/ English Abstract)	
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.					
EXAMINER				DATE CONSIDERED			

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.